



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:  
Chen et al.

Serial No. 10/712,460

Filed: 11/13/2003

For: Semiconductor Wafer  
Manufacturing Methods  
Employing Cleaning Delay Period

§ Group Art Unit: 1746  
§ Examiner: To be determined  
§ Customer No.: 000042717  
§ Attorney Docket No.:  
§ TSMC2002-1015/24061.42

PRELIMINARY AMENDMENT

Mail Stop Amendment  
Commissioner For Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

Prior to examination, please amend the above-identified patent application as follows:

**Amendments to the Specification** begin on page 2 of this paper.

**Remarks** begin on page 3 of this paper.